Accepted Manuscript

Electrodeposition of copper oxides (CuxOy) from acetate bath

Z. Mezine, A. Kadri, L. Hamadou, N. Benbrahim, A. Chaouchi

PII: S1572-6657(18)30230-3

DOI: doi:10.1016/j.jelechem.2018.03.055

Reference: JEAC 3971

To appear in: Journal of Electroanalytical Chemistry

Received date: 30 November 2017 Revised date: 25 March 2018 Accepted date: 26 March 2018

Please cite this article as: Z. Mezine, A. Kadri, L. Hamadou, N. Benbrahim, A. Chaouchi, Electrodeposition of copper oxides (CuxOy) from acetate bath. The address for the corresponding author was captured as affiliation for all authors. Please check if appropriate. Jeac(2017), doi:10.1016/j.jelechem.2018.03.055

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.



CCEPTED MANUSCRIPT

Electrodeposition of copper oxides (Cu_xO_y) from acetate bath

Z. Mezine¹, A. Kadri¹, L. Hamadou¹, N. Benbrahim¹ A. Chaouchi²

¹Laboratoire de Physique et Chimie des Matériaux (LPCM), Université Mouloud Mammeri

de Tizi- Ouzou (Algérie)

²Laboratoire de Chimie Appliquée et Génie Chimique de l'université Mouloud Mammeri de

Tizi-ouzou (Algérie)

Corresponding author: mezine2012@gmail.com

Abstract

Herein, we report the study of the electrodeposition of copper oxides mainly Cuprite (Cu₂O), paramelaconite Cu₄O₃ and tenorite (CuO) from a slightly acidic Cu(II) acetate solution on indium-doped tin oxide (ITO) substrate. A formation mechanism was proposed based on the observation of a series of reaction intermediates. The potential domain where the electrodeposition of copper oxides (CuxOv) is possible was investigated. The nucleation mechanism of (Cu₂O) during electrodeposition was studied as a function of Cu²⁺ concentrations and deposition potential by exploiting the electrochemical techniques such as cyclic voltammetry and chronoamperometry. This study enabled us to demonstrate that the nucleation process and the growth of dendrites obey the model of Scharifker and Hills 3D instantaneous under diffusion control. Morphological and structural characterizations of the electrodeposit are performed by scanning electron microscopy (SEM) and X-ray diffraction (XRD).

Keywords: copper oxides; paramelaconite; cuprite; ITO substrate; electrodeposition; nucleation model.

Download English Version:

https://daneshyari.com/en/article/6661833

Download Persian Version:

https://daneshyari.com/article/6661833

Daneshyari.com